

C L A I M

1. A device (1) for applying a liquid dopant solution on the surface of a wafer (3), which device (1) comprises a dopant distribution device (5), a rotatable dopant-transfer roll (7) horizontally translatable in a  
5 direction perpendicular to the axis of rotation (12) of the dopant-transfer roll (7) between a first roll position (15) and a second roll position (17), and a work table (9) for holding during normal operation the wafer (3) to be provided with the dopant solution,  
10 wherein the dopant distribution device (5) comprises a dopant-transfer block (20) supported by a block holder (21) and a fluid container (24) having an open side enclosed by an edge (26), which open side is directed to the dopant-transfer block (20) and which  
15 edge (26) cooperates with the dopant-transfer block (20), the block holder (21) or both to prevent leaking of dopant solution, wherein the block holder (21) and the fluid container (24) can be displaced relative to each other, wherein the block holder (21) is horizontally  
20 translatable in a direction perpendicular to the axis of rotation (12) of the dopant-transfer roll (7) between a first block position (30) in which the dopant-transfer block (20) is under the open side of the fluid container (24) and a second block position (31) in which  
25 the dopant-transfer block (20) has contacted the rotatable dopant-transfer roll (7) in its first roll position (15), wherein during normal operation in the second roll position (17) the rotatable dopant-transfer roll (7) has contacted the wafer (3) to provide dopant  
30 solution onto the surface of the wafer (3).